

Lithographic marker structure, lithographic projection apparatus comprising such a lithographic marker structure and method for substrate alignment using such a lithographic marker structure.

Abstract

Marker structure on a substrate for optical alignment of said substrate, said marker structure comprising a plurality of first structural elements and a plurality of second structural elements,

- 5 in use said marker structure allowing said optical alignment based upon
- providing at least one light beam directed on said marker structure,
 - detecting light received from said marker structure at a sensor,
 - determining alignment information from said detected light, said alignment
- information comprising information relating a position of said substrate to said sensor.

10 [Figure 3b]